

## WEST Search History

DATE: Wednesday, September 22, 2004

### **Hide? Set Name Query**

### **Hit Count**

*DB=USPT; PLUR=YES; OP=ADJ*

<input type="checkbox"/>	L3	L1 and 134/\$.ccls.	19
<input type="checkbox"/>	L2	L1 and 134/.ccls.	0
<input type="checkbox"/>	L1	quartz with (metal or steel or aluminum) with wall	651

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L5: Entry 10 of 11

File: USPT

May 26, 1992

DOCUMENT-IDENTIFIER: US 5115576 A

TITLE: Vapor device and method for drying articles such as  
semiconductor wafers with substances such as isopropyl alcohol

[Current US Cross Reference Classification](#) (1):  
[134/21](#)

## CLAIMS:

3. A device according to claim 1, where said vacuum process chamber  
includes a quartz liner.

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L3: Entry 1 of 19

File: USPT

Mar 16, 2004

DOCUMENT-IDENTIFIER: US 6706334 B1

TITLE: Processing method and apparatus for removing oxide film

Detailed Description Text (35):

The treatment vessel 110 is constituted of aluminum materials and its inner wall is provided with quartz (SiO.sub.2) linings 113 and 114 to be protected from metal pollution, erosion or the like. The treatment vessel 110 can be formed as a housing whose transverse plane may have various shapes such as a circle, a square and a polygon. A bottom plate 112 having a predetermined thickness is fixed to the bottom of the treatment vessel 110. A base 129 is disposed on the bottom plate 112, and a cylindrical susceptor 120 is provided on the base 129. The wafer W is placed on the top of the susceptor 120 and clamped by a quartz-made clamp ring 121. A jacket (or a pipe) 122 for holding a chiller and a heat exchanger 123 are included in the susceptor 120. The jacket 122 and heat exchanger 123 can be formed integrally as one component. The chiller is supplied from a chiller supply unit 142 into the jacket 122 through a cooling pipe 143 to cool the wafer W down to a given temperature, such as a temperature not higher than room temperature.

Current US Cross Reference Classification (1):134/1.1Current US Cross Reference Classification (2):134/1.2Current US Cross Reference Classification (3):134/3[Previous Doc](#)[Next Doc](#)[Go to Doc#](#)

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L2: Entry 1 of 1

File: DWPI

Jan 28, 1998

DERWENT-ACC-NO: 1996-334173

DERWENT-WEEK: 200328

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TITLE: Wet chemical treatment installation for substrate plates - has lifting device with respective transport carriages for substrate plates and substrate plate holder

INVENTOR: DURST, J; SCHULZ, W ; SIGEL, H

## PATENT-ASSIGNEE:

ASSIGNEE

CODE

STEAG MICROTECH GMBH DONAUESCHINGEN

STGG

STEAG MICROTECH GMBH

STGG

STEAGMICRO TECH GMBH

STGG

PRIORITY-DATA: 1995DE-1046990 (December 15, 1995), 1995DE-1000239 (January 5, 1995)

[Search Selected](#)[Search ALL](#)[Clear](#)

## PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
<input type="checkbox"/> <a href="#">CN 1171858 A</a>	January 28, 1998		000	H01L021/00
<input type="checkbox"/> <a href="#">WO 9621241 A1</a>	July 11, 1996	G	045	H01L021/00
<input type="checkbox"/> <a href="#">DE 19546990 A1</a>	July 11, 1996		021	B65G049/04
<input type="checkbox"/> <a href="#">DE 19546990 C2</a>	July 3, 1997		018	B65G049/04
<input type="checkbox"/> <a href="#">DE 19549487 A1</a>	August 7, 1997		045	B65G049/04
<input type="checkbox"/> <a href="#">FI 9702733 A</a>	June 25, 1997		000	H01L000/00
<input type="checkbox"/> <a href="#">DE 19549488 A1</a>	September 4, 1997		000	B65G049/04
<input type="checkbox"/> <a href="#">DE 19549490 A1</a>	September 11, 1997		001	B65G049/04
<input type="checkbox"/> <a href="#">EP 801814 A1</a>	October 22, 1997	G	000	H01L021/00
<input type="checkbox"/> <a href="#">JP 10503327 W</a>	March 24, 1998		040	H01L021/304
<input type="checkbox"/> <a href="#">KR 98701133 A</a>	April 30, 1998		000	H01L021/00
<input type="checkbox"/> <a href="#">US 5902402 A</a>	May 11, 1999		000	B05C003/00
<input type="checkbox"/> <a href="#">JP 3088463 B2</a>	September 18, 2000		016	H01L021/304

<input type="checkbox"/> <u>DE 19549487 C2</u>	November 16, 2000	000	B65G049/04
<input type="checkbox"/> <u>DE 19549490 C2</u>	January 18, 2001	000	B65G049/04
<input type="checkbox"/> <u>TW 399224 A</u>	July 21, 2000	000	H01L021/00
<input type="checkbox"/> <u>DE 19549488 C2</u>	August 2, 2001	000	B65G049/04
<input type="checkbox"/> <u>EP 801814 B1</u>	August 29, 2001	G 000	H01L021/00
<input type="checkbox"/> <u>DE 59509568 G</u>	October 4, 2001	000	H01L021/00
<input type="checkbox"/> <u>KR 275166 B</u>	January 15, 2001	000	H01L021/00

DESIGNATED-STATES: CA CN FI JP KR SG US AT BE CH DE DK ES FR GB GR IE  
IT LU MC NL PT SE AT BE CH DE DK ES FR GB GR IE IT LI LU NL PT SE AT BE  
CH DE DK ES FR GB GR IE IT LI LU NL PT SE

CITED-DOCUMENTS:EP 523836; FR 2586658 ; GB 2178594 ; US 5301700

## APPLICATION-DATA:

PUB-NO	APPL-DATE	APPL-NO	DESCRIPTOR
CN 1171858A	December 29, 1995	1995CN-0197255	
CN 1171858A	December 29, 1995	1995WO-EP05153	
CN 1171858A		WO 9621241	Based on
WO 9621241A1	December 29, 1995	1995WO-EP05153	
DE 19546990A1	December 15, 1995	1995DE-1046990	
DE 19546990C2	December 15, 1995	1995DE-1046990	
DE 19549487A1	December 15, 1995	1995DE-1046990	Div ex
DE 19549487A1	December 15, 1995	1995DE-1049487	
DE 19549487A1		DE <u>19546990</u>	Div ex
FI 9702733A	December 29, 1995	1995WO-EP05153	
FI 9702733A	June 25, 1997	1997FI-0002733	
DE 19549488A1	December 15, 1995	1995DE-1046990	Div ex
DE 19549488A1	December 15, 1995	1995DE-1049488	
DE 19549488A1		DE <u>19546990</u>	Div ex
DE 19549490A1	December 15, 1995	1995DE-1046990	Div ex
DE 19549490A1	December 15, 1995	1995DE-1049490	
DE 19549490A1		DE <u>19546990</u>	Div ex
EP 801814A1	December 29, 1995	1995EP-0943224	
EP 801814A1	December 29, 1995	1995WO-EP05153	
EP 801814A1		WO 9621241	Based on
JP 10503327W	December 29, 1995	1995WO-EP05153	
JP 10503327W	December 29, 1995	1996JP-0520722	
JP 10503327W		WO 9621241	Based on
KR 98701133A	December 29, 1995	1995WO-EP05153	
KR 98701133A	July 1, 1997	1997KR-0704546	
KR 98701133A		WO 9621241	Based on
US 5902402A	December 29, 1995	1995WO-EP05153	

US 5902402A	July 3, 1997	1997US-0875408	
US 5902402A		WO 9621241	Based on
JP 3088463B2	December 29, 1995	1995WO-EP05153	
JP 3088463B2	December 29, 1995	1996JP-0520722	
JP 3088463B2		JP 10503327	Previous Publ.
JP 3088463B2		WO 9621241	Based on
DE 19549487C2	December 15, 1995	1995DE-1046990	Div ex
DE 19549487C2	December 15, 1995	1995DE-1049487	
DE 19549487C2		DE <u>19546990</u>	Div ex
DE 19549490C2	December 15, 1995	1995DE-1046990	Div ex
DE 19549490C2	December 15, 1995	1995DE-1049490	
DE 19549490C2		DE <u>19546990</u>	Div ex
TW 399224A	January 5, 1996	1996TW-0100109	
DE 19549488C2	December 15, 1995	1995DE-1046990	Div ex
DE 19549488C2	December 15, 1995	1995DE-1049488	
DE 19549488C2		DE <u>19546990</u>	Div ex
EP 801814B1	December 29, 1995	1995EP-0943224	
EP 801814B1	December 29, 1995	1995WO-EP05153	
EP 801814B1		WO 9621241	Based on
DE 59509568G	December 29, 1995	1995DE-0509568	
DE 59509568G	December 29, 1995	1995EP-0943224	
DE 59509568G	December 29, 1995	1995WO-EP05153	
DE 59509568G		EP 801814	Based on
DE 59509568G		WO 9621241	Based on
KR 275166B	December 29, 1995	1995WO-EP05153	
KR 275166B	July 1, 1997	1997KR-0704546	
KR 275166B		KR 98701133	Previous Publ.
KR 275166B		WO 9621241	Based on

399224 A , DE 19549488 C2 INT-CL (IPC): B05C 3/00; B65G 49/04; B65G 49/07; H01L 0/00; H01L 21/00; H01L 21/30; H01L 21/304; H01L 21/306; H01L 21/68

ABSTRACTED-PUB-NO: EP 801814B  
BASIC-ABSTRACT:

The installation (20) has a container (21) holding the treatment fluid (23) into which a holder (17) for the substrate plates (25) is lowered. Continuous lifting in and out of the substrate plate holder and the substrate plates relative to the treatment fluid is obtained via a lifting device with one transport carriage for the substrate plates and a second transport carriage for the holder.

The transport carriages for the substrate plates and the holder are coupled together via a linkage and displaced relative to a vertical guide rail, with the lifting drive acting on the first transport carriage.

USE - For uniform surface treatment of silicon wafers.  
ABSTRACTED-PUB-NO:

US 5902402A  
EQUIVALENT-ABSTRACTS:

The installation (20) has a container (21) holding the treatment fluid (23) into which a holder (17) for the substrate plates (25) is lowered. Continuous lifting in and out of the substrate plate holder and the substrate plates relative to the treatment fluid is obtained via a lifting device with one transport carriage for the substrate plates and a second transport carriage for the holder.

The transport carriages for the substrate plates and the holder are coupled together via a linkage and displaced relative to a vertical guide rail, with the lifting drive acting on the first transport carriage.

USE - For uniform surface treatment of silicon wafers.

The installation (20) has a container (21) holding the treatment fluid (23) into which a holder (17) for the substrate plates (25) is lowered. Continuous lifting in and out of the substrate plate holder and the substrate plates relative to the treatment fluid is obtained via a lifting device with one transport carriage for the substrate plates and a second transport carriage for the holder.

The transport carriages for the substrate plates and the holder are coupled together via a linkage and displaced relative to a vertical guide rail, with the lifting drive acting on the first transport carriage.

USE - For uniform surface treatment of silicon wafers.

WO 9621241A

CHOSEN-DRAWING: Dwg.3/16

TITLE-TERMS: WET CHEMICAL TREAT INSTALLATION SUBSTRATE PLATE LIFT  
DEVICE RESPECTIVE TRANSPORT CARRIAGE SUBSTRATE PLATE SUBSTRATE PLATE  
HOLD

DERWENT-CLASS: P42 Q35 U11

EPI-CODES: U11-C06A1B; U11-C07B;

SECONDARY-ACC-NO:  
Non-CPI Secondary Accession Numbers: N1996-281583

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